



500.37328CX1

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): YOKOGAWA, et al

Serial No.: 09/336,687 (CPA)

Filed: June 21, 1999

For: PLASMA PROCESSING SYSTEM AND METHOD

Group: 1763

Examiner: L. Alejandro

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Commissioner for Patents
Washington, D.C. 20231

November 5, 2001

Sir:

The following preliminary amendments and remarks are respectfully submitted in connection with the above-identified CPA and is responsive to the Office Action dated July 3, 2001.

IN THE CLAIMS:

Please amend claim 33 as follows:

33. (twice amended) A plasma etching system in accordance with Claim 3, wherein:

B' the vacuum chamber includes an upper section made of an insulating material;

inventor

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